

AF 117564  
Patent

Attorney's Docket No. 027260-295

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: PHOTOMASK, FABRICATION  
METHOD OF PHOTOMASK, AND  
FABRICATION METHOD OF  
SEMICONDUCTOR INTEGRATED  
CIRCUIT

Group Art Unit: 1756

Examiner: S. Mohamedulla

Confirmation: 5658

6/6/02  
#19 Notice  
of  
Appeal**NOTICE OF APPEAL**Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

All finally rejected claims in the decision of the Primary Examiner dated dated January 3, 2002 are hereby appealed to the Board of Patent Appeals and Interferences.

☐ The Appeal fee was previously paid on \_\_\_\_\_.

Therefore, no Appeal fee is now required.

☐ Small entity status is hereby claimed.

☒ Enclosed is the Appeal fee of ☐ \$160.00 (219) ☒ \$320.00 (119).

☐ Please charge the Appeal fee of ☐ \$160.00 (219) ☐ \$320.00 (119) to Deposit  
Account No. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

BURNS, DOANE, SWECKER &amp; MATHIS, L.L.P.

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